IBS Center for Multidimensional Carbon Materials

Special Guest Speaker

Dr.Seong Keun KIM

Principle Research Scientist
Center for Electronic Materials
Korea Institute of Science and Technology
s.k.kim@kist.re.kr
http://electrocera.kist.re.kr

Principle and applications of atomic layer deposition for electronic devices

JUNE 16
2 P.M.

Bldg. 101
Seminar room on the 1st floor

Atomic layer deposition (ALD) is a thin film growth technique based on the self-limited chemical reaction, which offers atomic-level controllability. ALD has attracted considerable attention as a method for growing thin films for various applications on account of its excellent thickness controllability, conformal growth on the complex-shaped structures, uniform film growth on large area substrates, low growth temperature and very low pinhole density. In this presentation, I will introduce the principle of ALD reaction of oxides and metals. My research progress for memory and display applications will be introduced.

<Research Field>

-DRAM capacitor
-Atomic Layer Deposition
-Dielectric thin film
-Nitride & oxide thin films

You are cordially invited to attend!